

L Number	Hits	Search Text	DB	Time stamp
1	11	("5619548" or "5689614").pn. or ep-1066925-\$.did. or wo-9941434-\$.did. or wo-199941434-\$.did. or wo-9925004-\$.did. or wo-199925004-\$.did. or ep-1065567-\$.did. or wo200109566-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/23 16:03
2	33471	developing same (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/23 16:04
3	69	(developing same (wafer or substrate)) and (scatterometry or reflectometry)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/23 16:04
4	44	((developing same (wafer or substrate)) and (scatterometry or reflectometry)) and (cd or critical adj dimension or endpoint)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/23 16:13
5	20	((developing same (wafer or substrate)) and (scatterometry or reflectometry)) and endpoint	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/23 16:14
6	347	(developing same (wafer or substrate)) and endpoint	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/23 16:14
7	327	((developing same (wafer or substrate)) and endpoint) not (((developing same (wafer or substrate)) and (scatterometry or reflectometry)) and (cd or critical adj dimension or endpoint)) or (((developing same (wafer or substrate)) and (scatterometry or reflectometry)) and endpoint))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/23 16:14
8	209	(((developing same (wafer or substrate)) and endpoint) not (((developing same (wafer or substrate)) and (scatterometry or reflectometry)) and (cd or critical adj dimension or endpoint)) or (((developing same (wafer or substrate)) and (scatterometry or reflectometry)) and endpoint))) and endpoint same (detect\$3 or determin\$5 or sens\$3 or measur\$3 or monitor\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/23 16:16
9	1		USPAT	2003/07/23 16:19
10	1		USPAT	2003/07/23 16:19
11	1		USPAT	2003/07/23 16:20
12	1		USPAT	2003/07/23 16:20